



Contribution ID: 94

Type: POSTER

Observation of iron impurities diffusion in silicon under bending stress by Mössbauer spectroscopy

Experiment

Are you a student, a delegate from developing countries or a participant with physical needs and would like to apply for a sponsored accomodation. Please answer with yes or no.

no

Please specify whether you would prefer an oral or poster contribution.

oral

Primary author: Dr SUZUKI, Kunifumi (Tokyo Institute of Technology)

Co-authors: HAYAKAWA, Kazuo (Shizuoka Institute of Science and Technology); YUKIHIRA, Kenichi (Shizuoka Institute of Science and Technology); Prof. ASAHI, Koichiro (Tokyo Institute of Technology); Mr ICHINO, Masahiro (Shizuoka Institute of Science and Technology); Prof. YOSHIDA, Yutaka (Shizuoka Institute of Science and Technology)

Presenter: Dr SUZUKI, Kunifumi (Tokyo Institute of Technology)

Track Classification: Semiconductors, Metals and Insulators